

Dinesh Pamunuwa^{*}, Matt Grange^{**}, Axel Jantsch⁺,
Sunil Rana^{*}, Tyson Tian Qin^{*}

^{*}University of Bristol, Bristol UK

^{**}Mentor Graphics, USA

⁺KTH Royal Institute of Technology, Stockholm, Sweden

System Performance Analysis for Heterogeneous 3-D ICs and Emerging Technologies

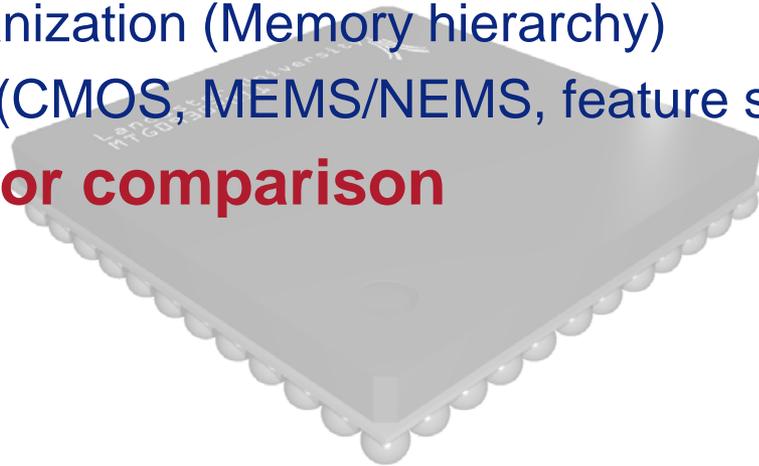


microelectronics research group



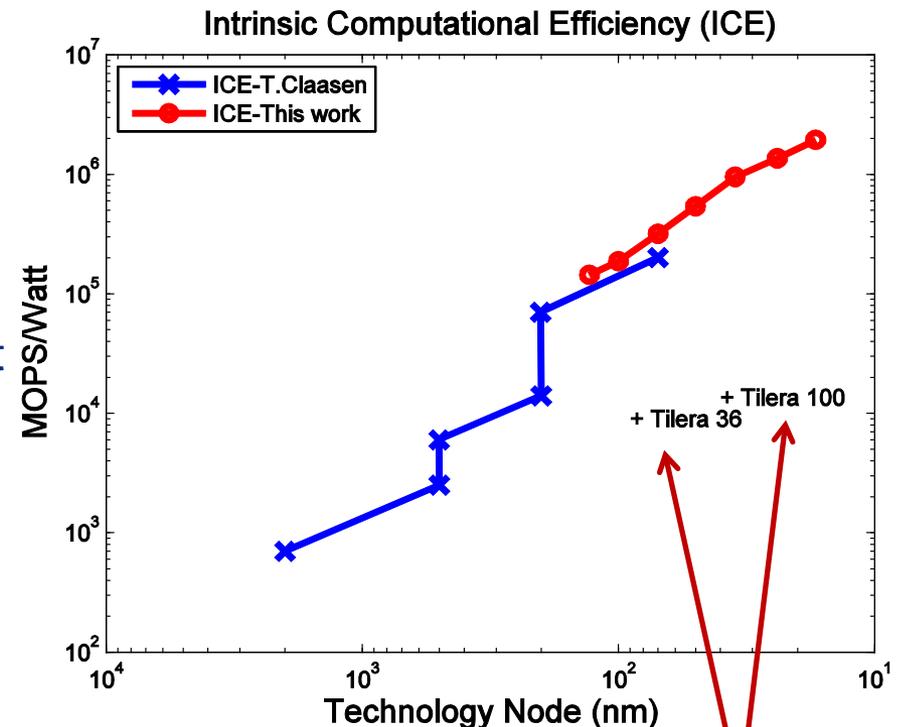
Future Direction of 3-D ICs

- ❑ **3-D ICs promise performance / cost advantages for high performance digital applications as well as enhanced functionality**
- ❑ **A staggering amount of degrees of freedom exist**
 - Packages (2-D, Multi-chip Modules, 3-D die stacks)
 - Digital architecture (single to multi to many-core)
 - Routing architectures (buses, Networks-on-Chip, hybrids)
 - System organization (Memory hierarchy)
 - Technology (CMOS, MEMS/NEMS, feature size reduction)
- ❑ **Framework for comparison**



Intrinsic Computational Efficiency

- **The Intrinsic Computational Efficiency (ICE), proposed by T. Claasen, creates the maximum upper bound for computational capability of a silicon-based processor.**
 - The entire silicon area of a processor is filled with the most fundamental computational unit, in this case we have used 32-bit adders.
 - A real system could never achieve the same performance per Watt because this metric ignores the overhead of control circuitry, interconnect, and memory.



Two recent multi-core processors

Expanding the *ICE* to the *ECE*

- ❑ The *ICE* gives the *maximum upper bound* on efficiency, but cannot account for realistic systems because it only considers the computational unit.
- ❑ We build upon the *ICE* by modelling the three fundamental operations of any processing unit:

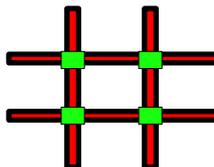
– The computational operation



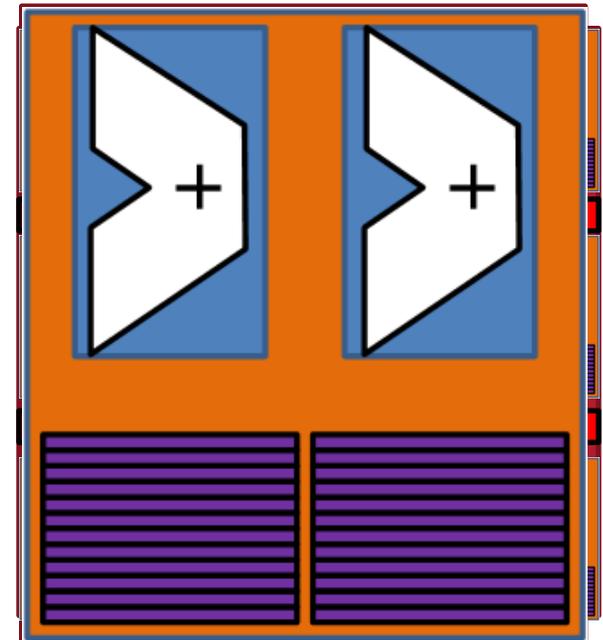
– The memory



– The interconnect



Processing Core

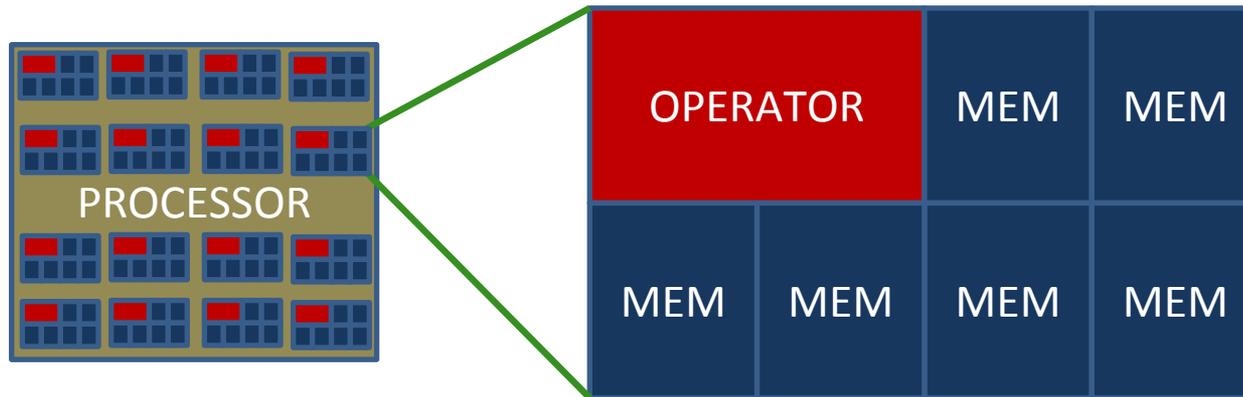


Temporal and Spatial Organization of Memory

5

□ μ_s

- Gives us the amount of memory per operator. Think of it as the amount of on-chip cache available

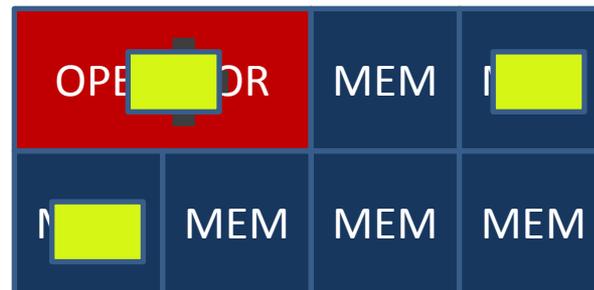


□ μ_T

- Gives us the number of memory reads/writes per operation.

2 reads, 1 write

$$\mu_T = 3$$

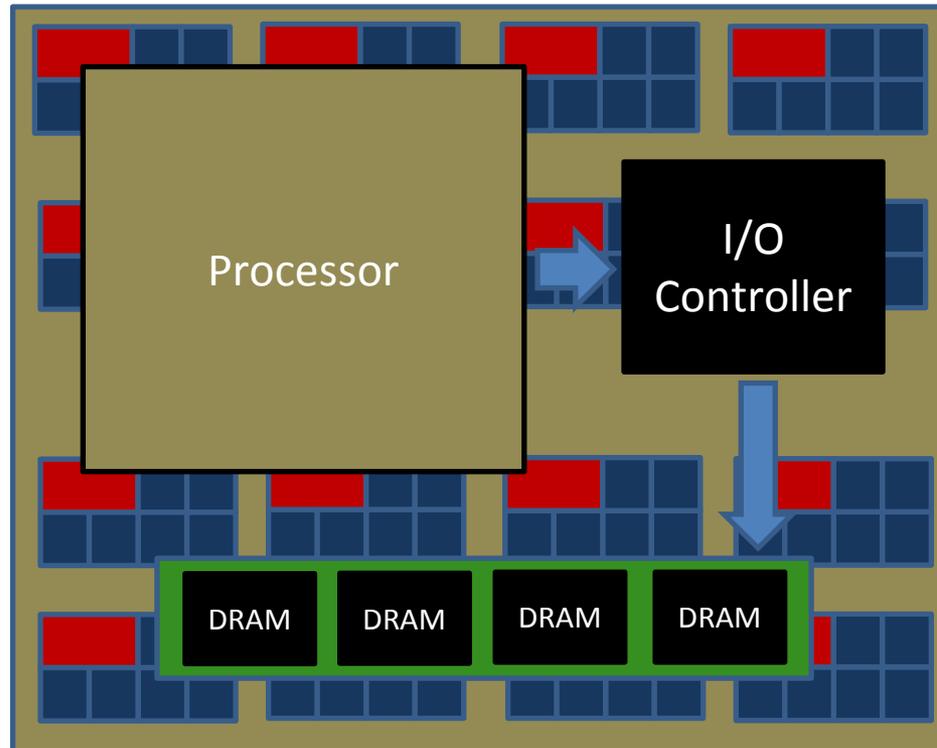


On- or Off-chip Memory?

□ ω (0-1)

- Gives the ratio of on- to off-chip memory in the system. Off-chip memory requires exiting the die with I/O drivers to external chips.

0: all-off-chip

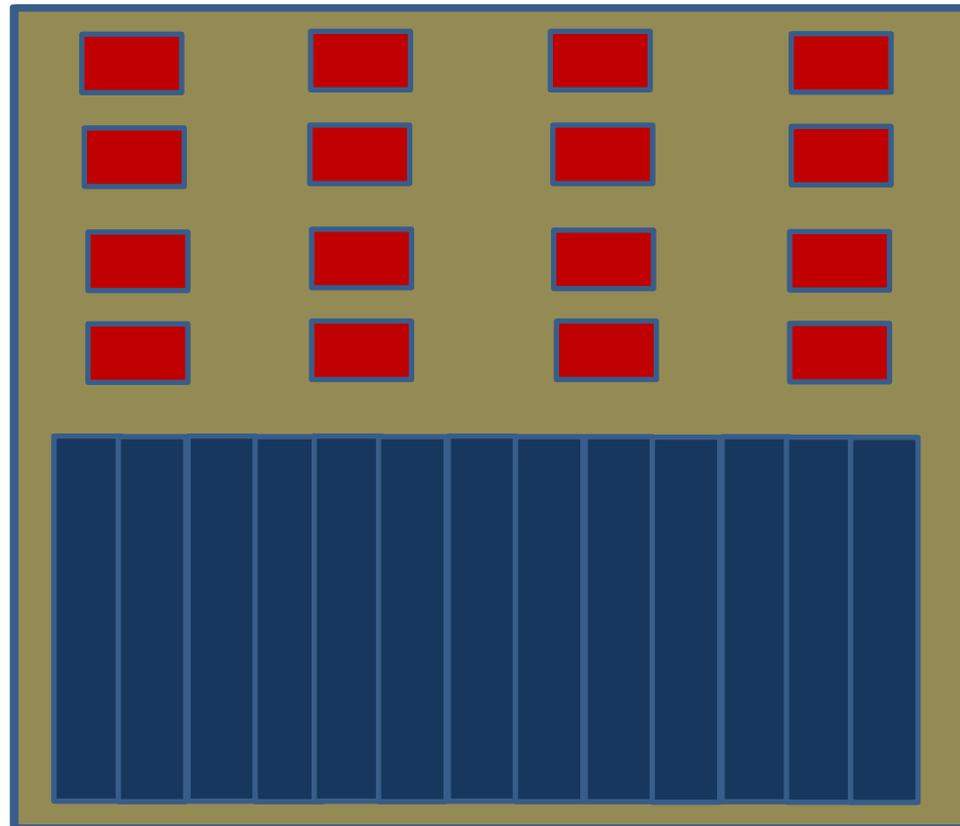


Memory Distribution Factor

□ Δ (0-1)

- Gives the distribution factor of the memory, or how close (local) it is the operator.

0:5 **ab-**
local



Effective Computational Efficiency

- For each computation we must consider the expense of energy for the operation, interconnect (on and off-chip) and memory reads/writes.

Number of Memory Accesses/op

Energy for a 32-bit addition

On-chip memory energy

Off-chip memory energy

$$EE_{arch}^{tn} = E_{32}^{tn} + \mu_T (\omega (e_1 + \Delta \times E_{int}^{tn}_{arch}) + (1-\omega) (e_1 + E_{int}^{tn}_{arch} + E_{offchip}))$$

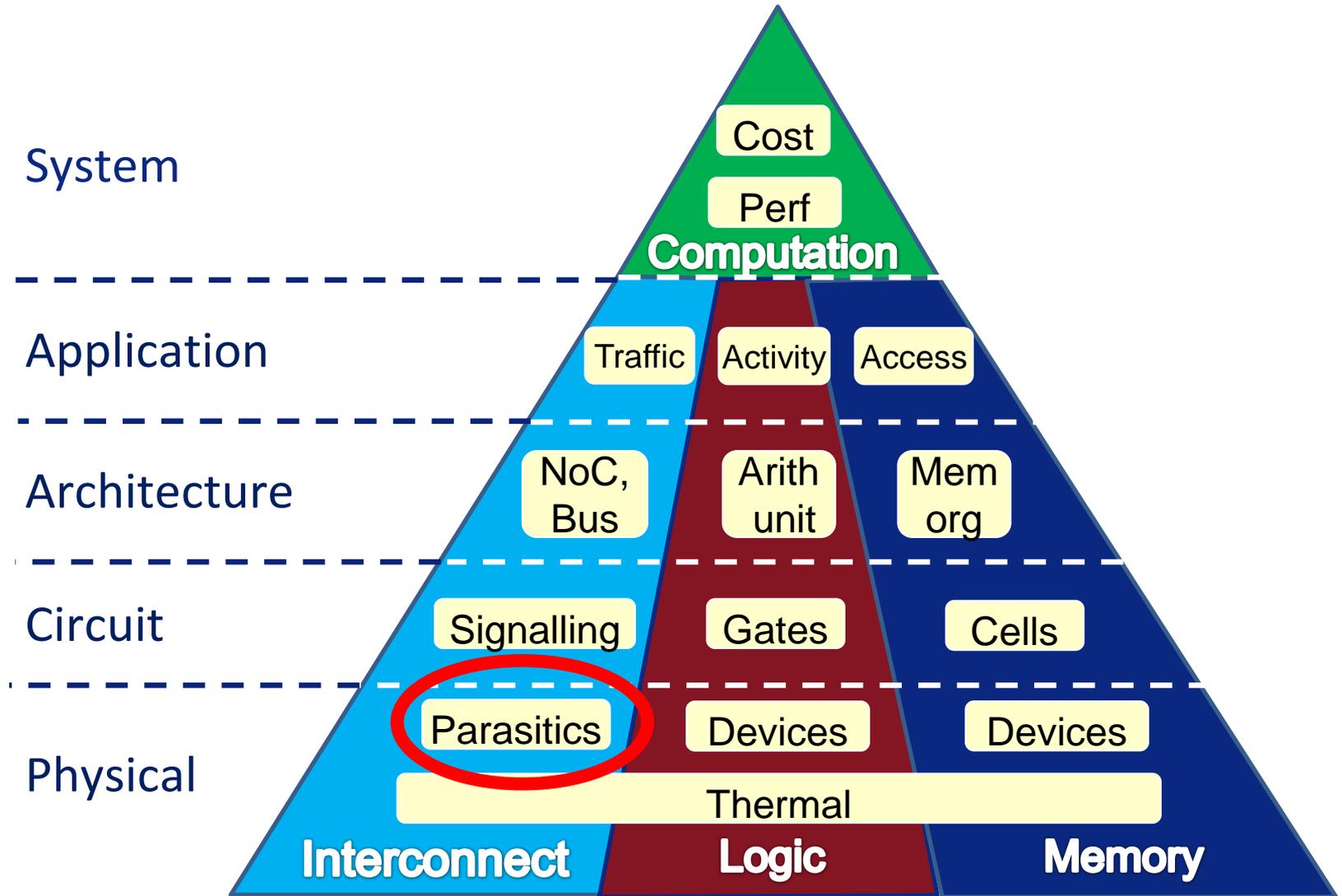
Ratio of on-chip : off-chip memory

$$ECE_{arch}^{tn} = \frac{1}{EE_{arch}^{tn}}$$

Amount of computation possible within the envelope of 1 Joule

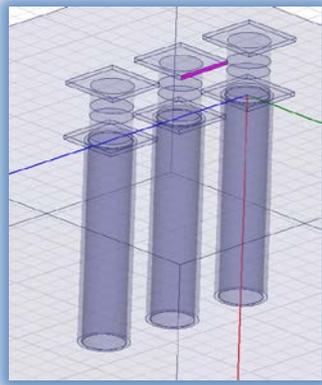
Modelling Hierarchy

9



Model Development

10

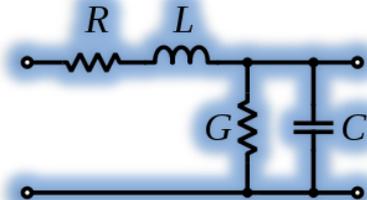
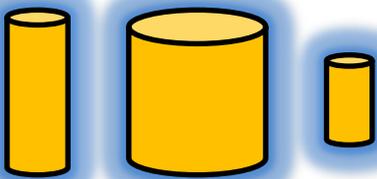
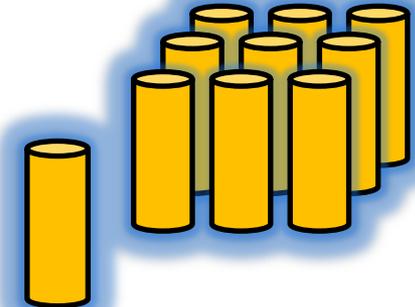


Parasitic Extraction (Q3D)

Resistance (R), Inductance (L)
Conductance (G), Capacitance (C)

Geometrical Sweeps
(length, radius, pitch, etc.)

Physical Sweeps
(Topology, Substrate, etc.)

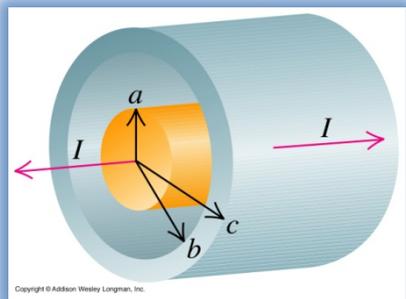


Data Manipulation (MATLAB)

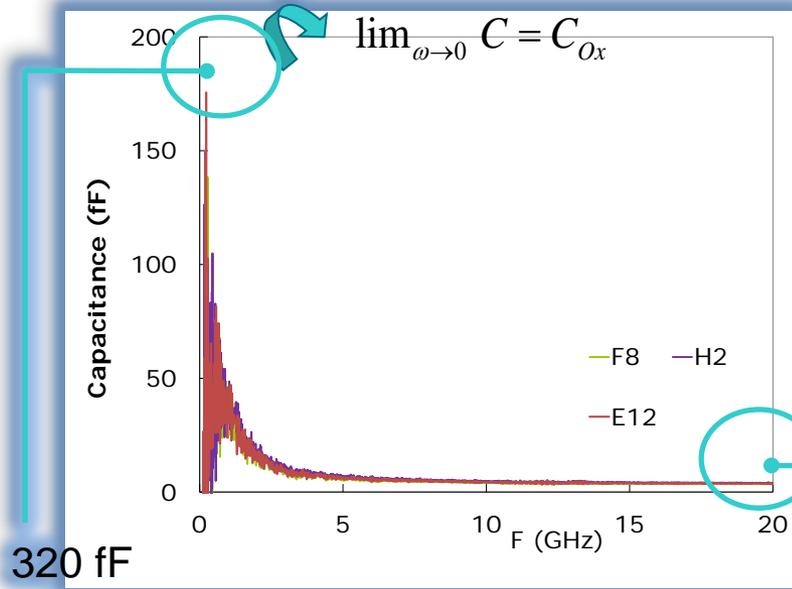
Physical Principles

Modelling

Verification

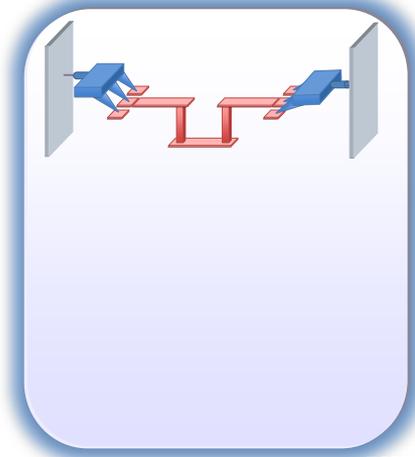
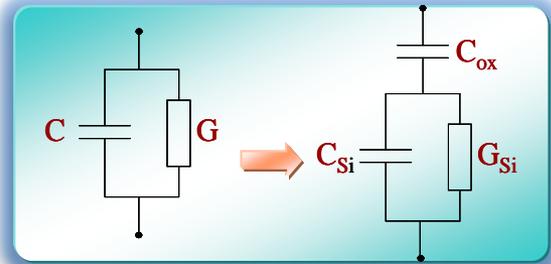


Model Verification



320 fF
(306.6)

4 fF
(4.5)



Stand-alone Parasitic Estimation Tool

12

Tools for Design Space Exploration of 3-D Integrated Circuits



Parasitic Extractor

Physical Parameters

TSV radius (μm)

TSV length (μm)

TSV spacing (μm)

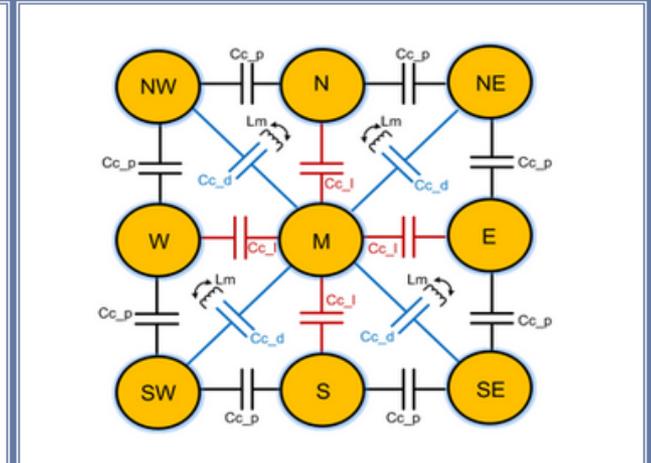
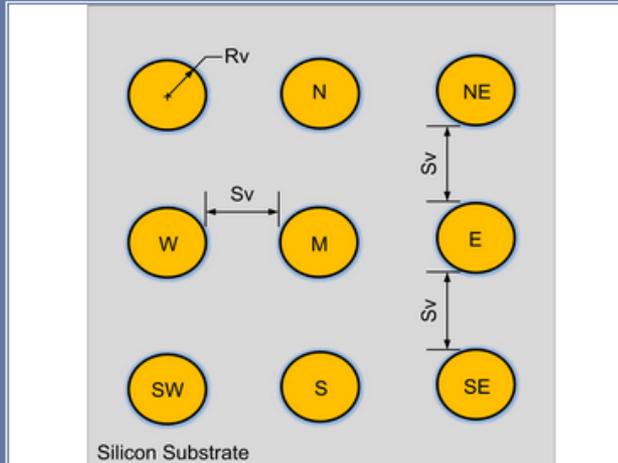
SiO₂ barrier thickness (μm)

Substrate type

TSV topology

[Help](#)

Generate Parasitics



Parasitic Data (Medium Resistive Substrate)

TSV location	R_s (m Ω)	L_s (pH)	C_s (fF)	L_{m_l} (pH)	L_{m_d} (pH)	C_{c_d} (fF)	C_{c_l} (fF)	C_{c_p} (fF)
Middle (M)	2.842	17.084	1785.985	8.962	6.932	12.017	80.857	
Lateral (N,S,E,W)	2.842	17.084	1630.928	8.962	6.932			104.223
Diagonal (NE,SE,NW,SW)	2.842	17.084	1229.846	8.962	6.932			104.223

Main

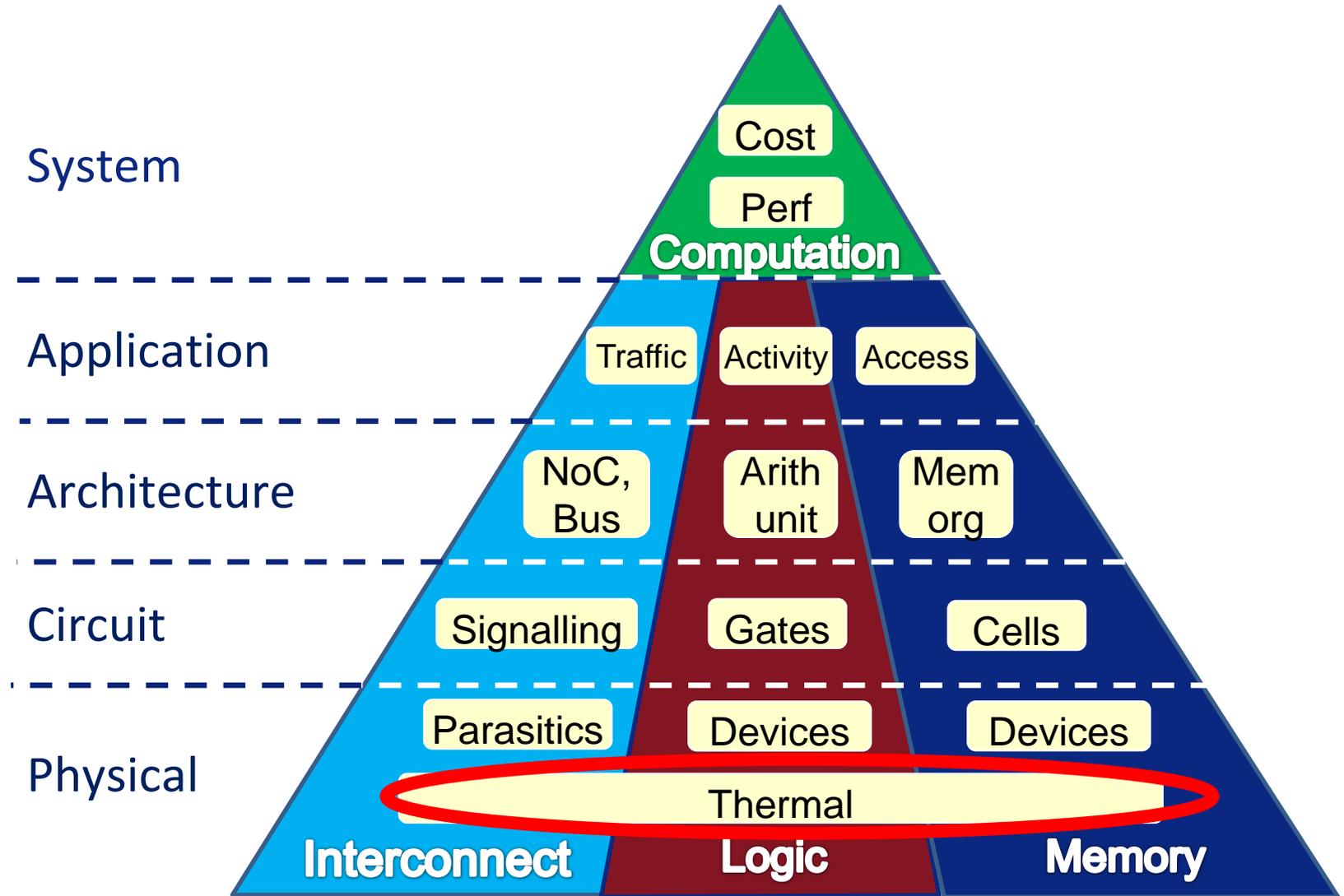
Parasitic Extraction

Thermal Estimation

Performance Estimation

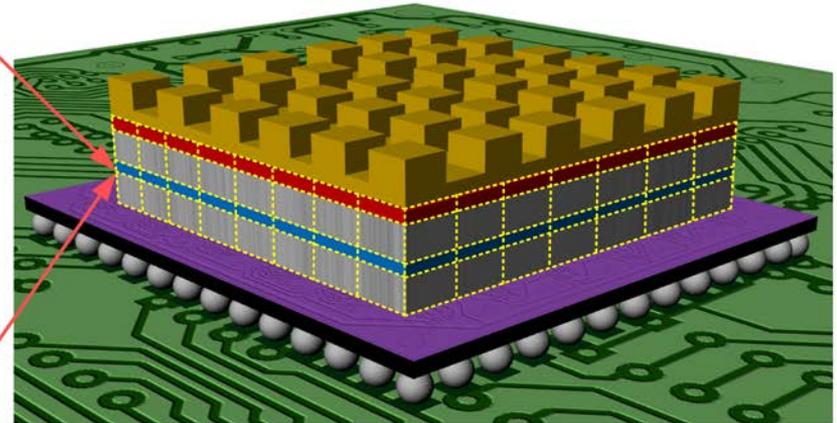
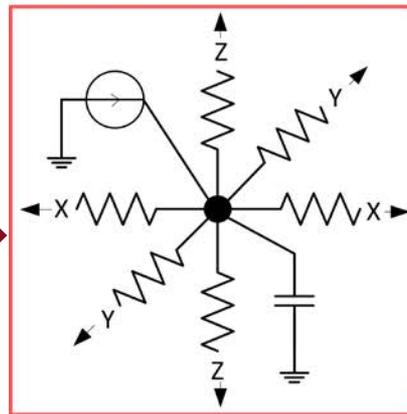
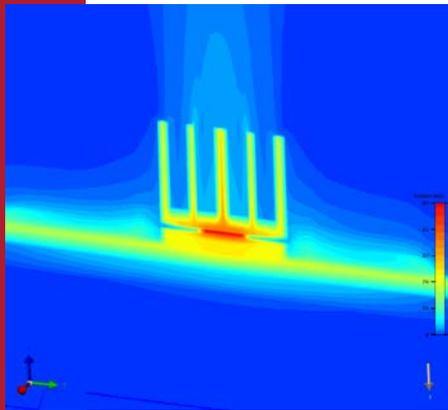
Modelling Hierarchy

15



Thermal Behaviour

- **Compact thermal models have been developed as part of the toolset to quickly predict the thermal behaviour.**
 - Verification based on comparison with results from a Computational Fluid Dynamic (CFD) solver (FloTHERM).
 - The thermal behaviour and limitations of 2-D and 3-D packages has been extracted from simulations.



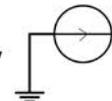
● Voltage at junction equivalent to temperature



Material Thermal Resistance



Material Thermal Absorption Capability (specific heat)



Power Injected into junction

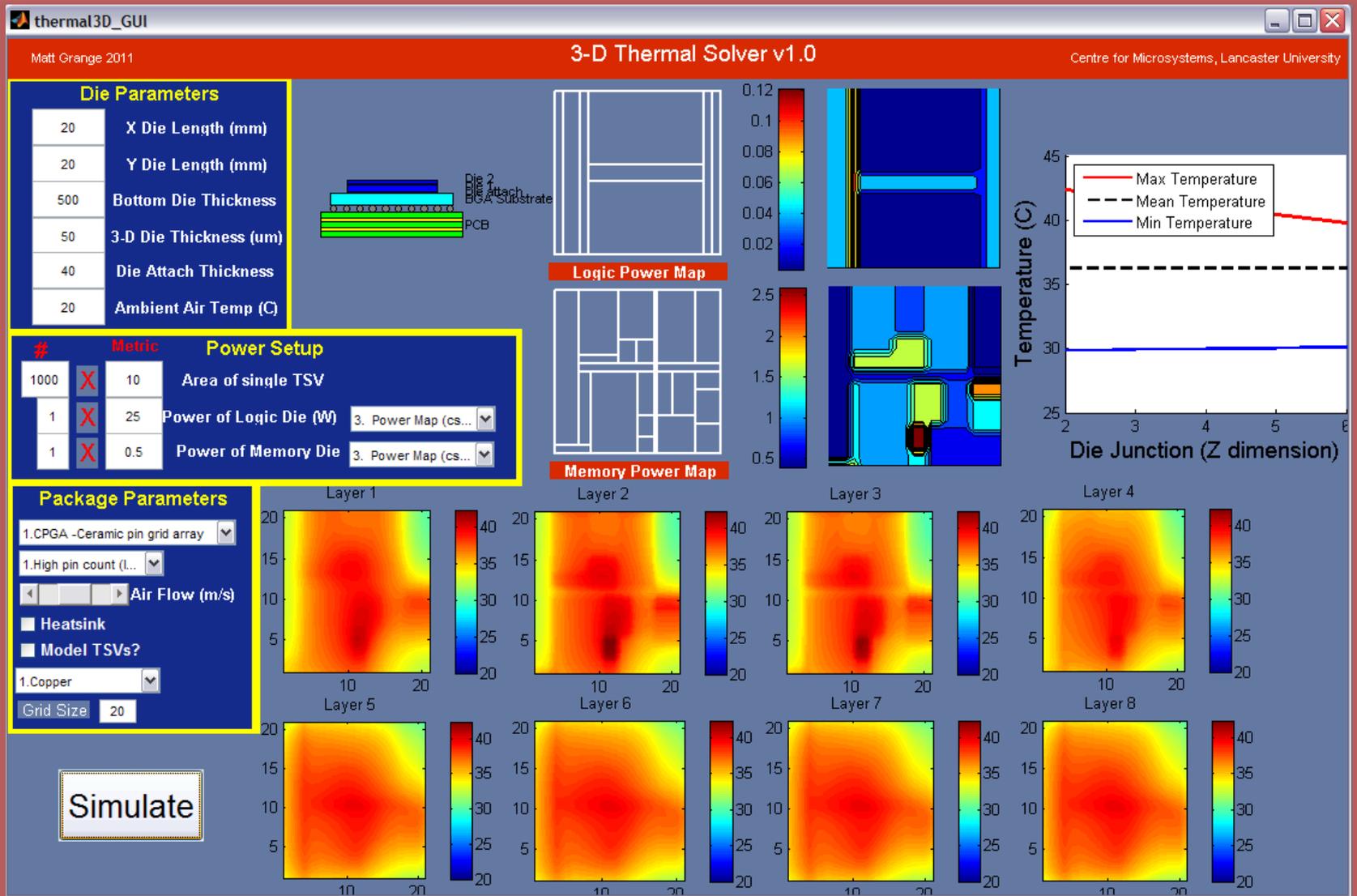
$$R_{th} = \frac{L}{kA}$$

$$T_j = qR_{th} + T_a$$

$$\theta_{j-a} = \frac{T_j - T_a}{q}$$

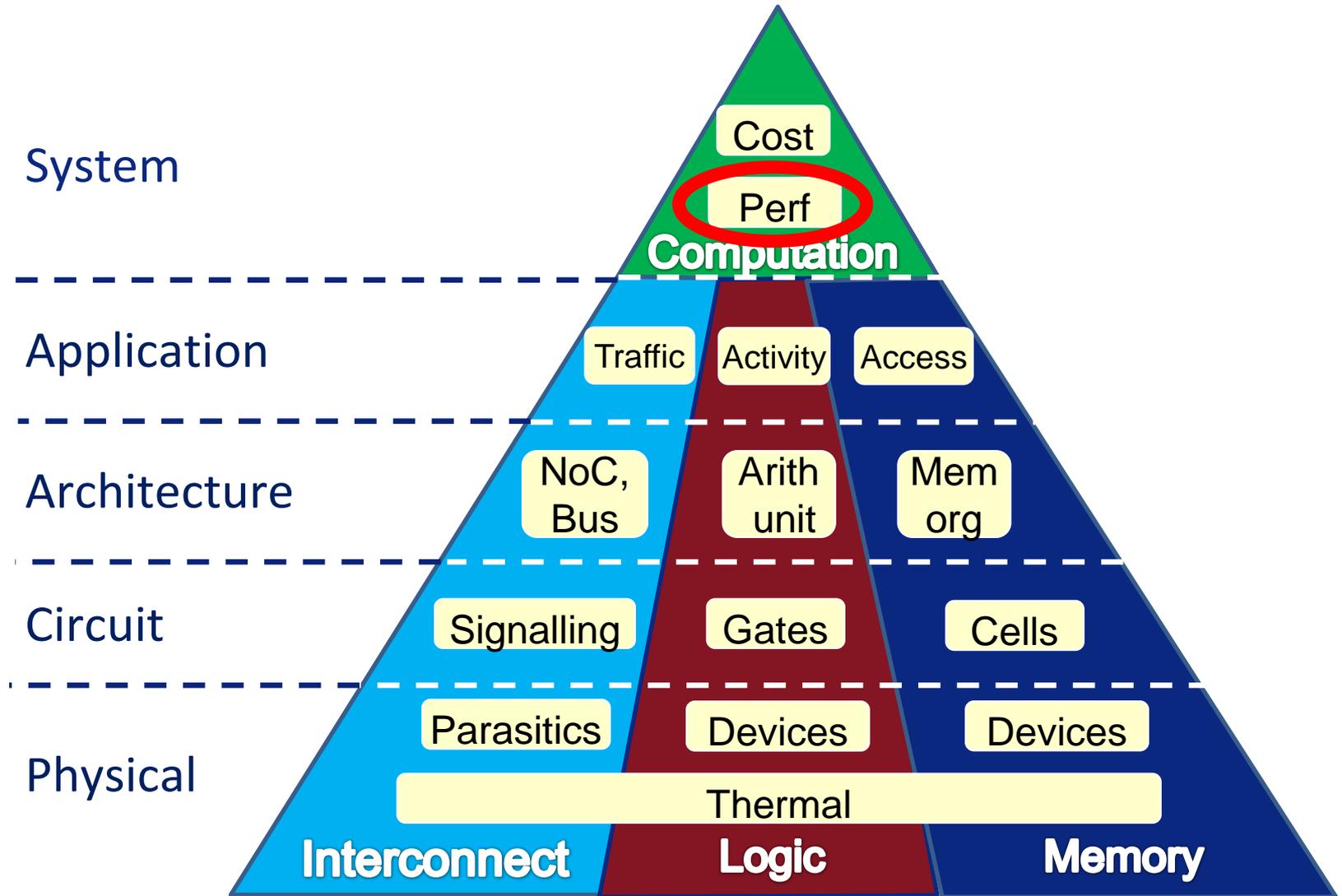
Stand-alone 3-D Thermal Tool

17



Modelling Hierarchy

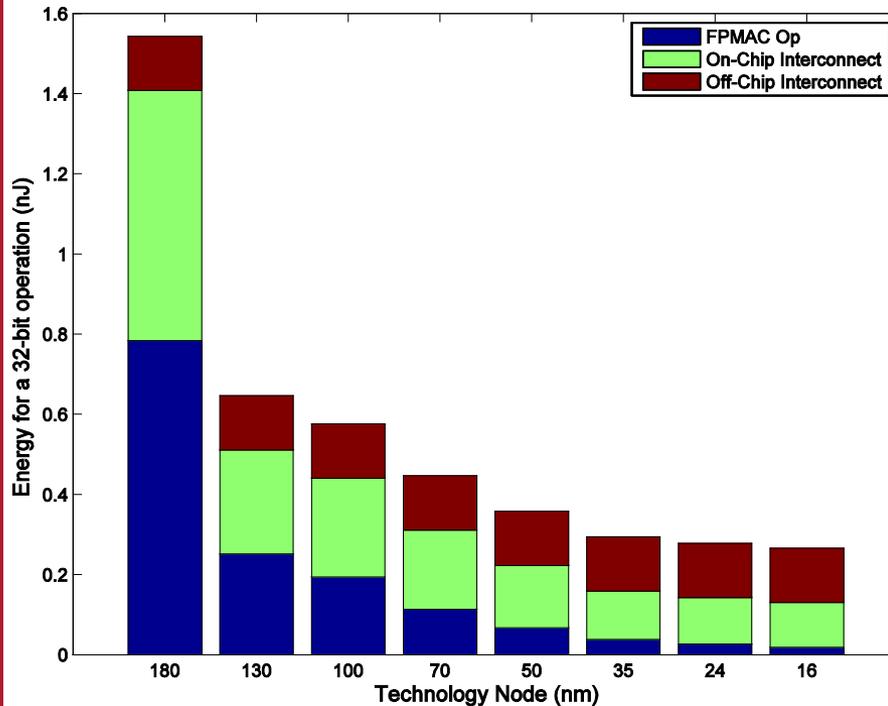
18



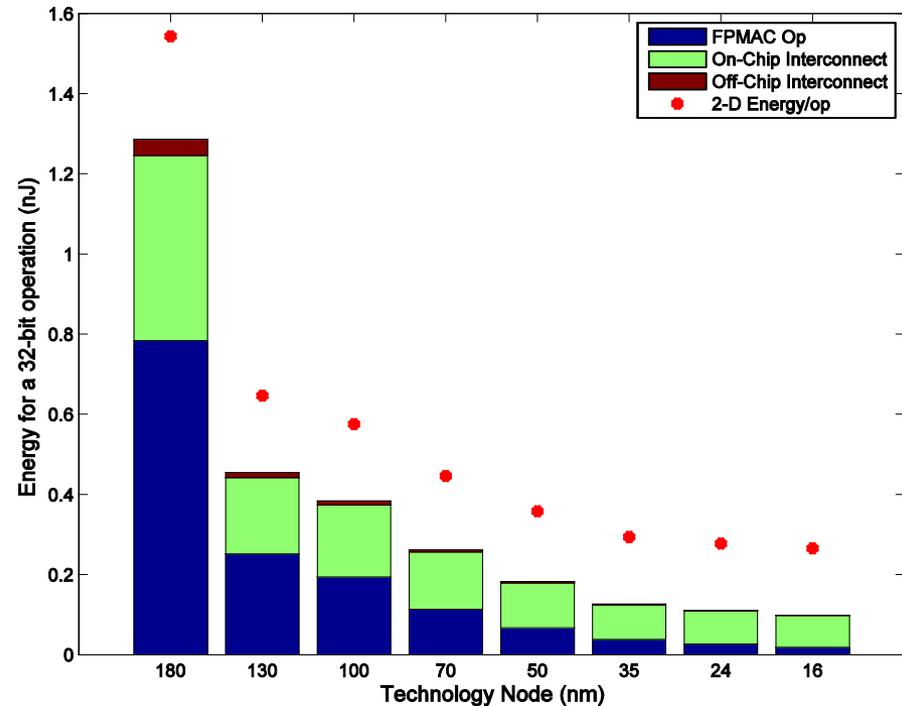
Scaling 2-D versus 3-D DRAM

19

2-D with off-chip DRAM



2-layer 3-D with in-stack DRAM



Fixed System: Intel 80 Core

20

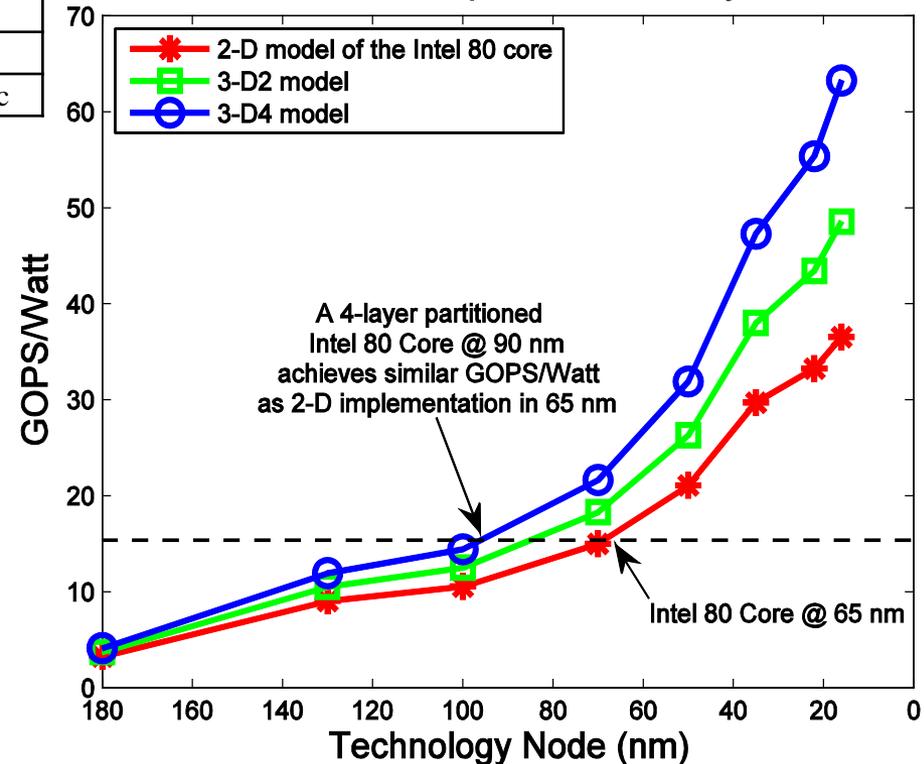
Param.	Type	Intel 80 Core	Equivalent
N	# of Layers	1 (2-D)	1-16 (3-D)
A	Die Area	12.64 × 21.72 mm	275 mm ² /N
tn	Tech. node	65 nm	180-17 nm
b	Data width	32-bit	32
μs	Memory/Operator	2K SRAM/2 FPU	1KB/Op
μt	Memory/Operation	App. Specific	01-Mar
σ	Bus Sharing Ratio	8x10 mesh/160 FPU	18/160=0.11
Δ	Memory Distribution	NoC Mesh	0.01-0.1
ω	On/off-chip mem	All on-chip	1
P	Power (W)	20-230	App. Specific

Implemented processors can be modelled by varying the parameters

The 4-layer 80-core 3-D system at 90 nm is still better than a 2-D system at 65 nm

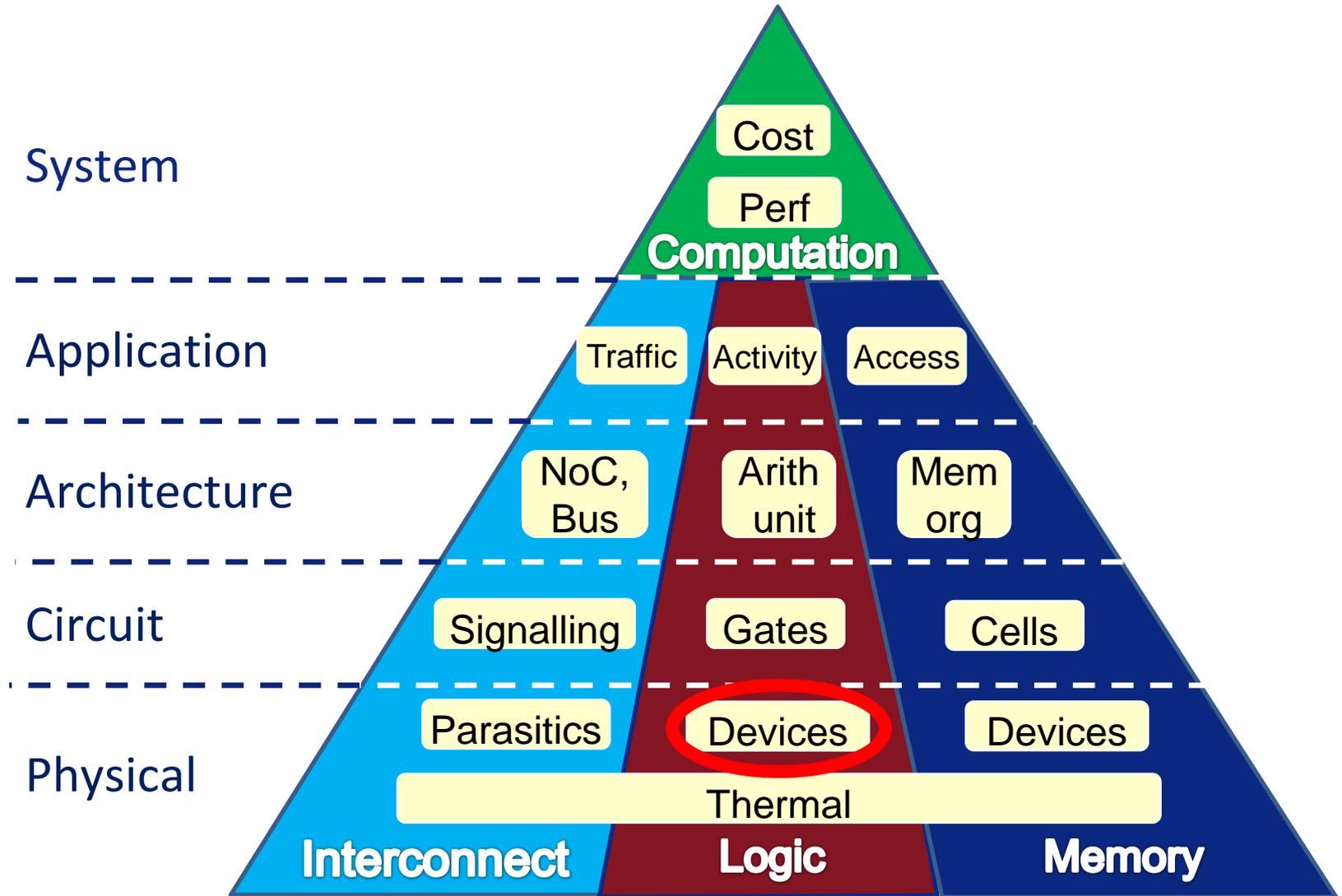
For every doubling of the stack height the computational efficiency increases by 20-30%

Effective Computational Efficiency



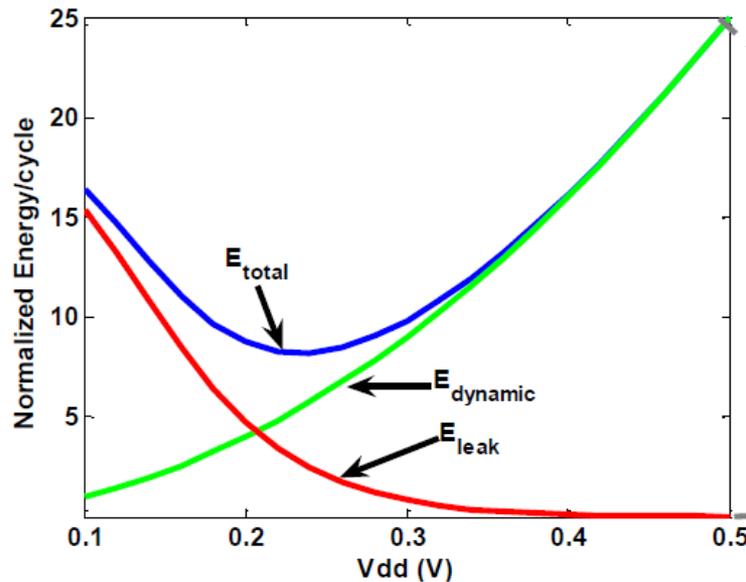
Modelling Hierarchy

21

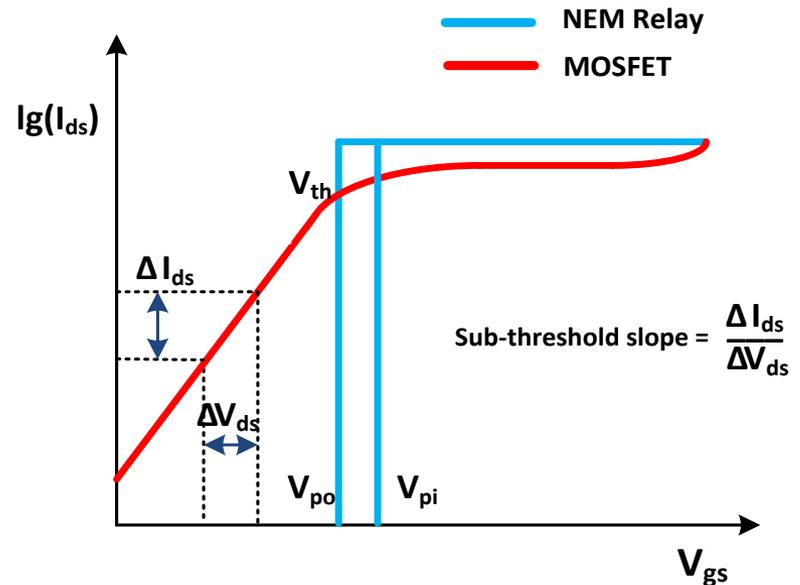


NEM Relay Based Computation

□ Limitation of CMOS Energy Efficiency



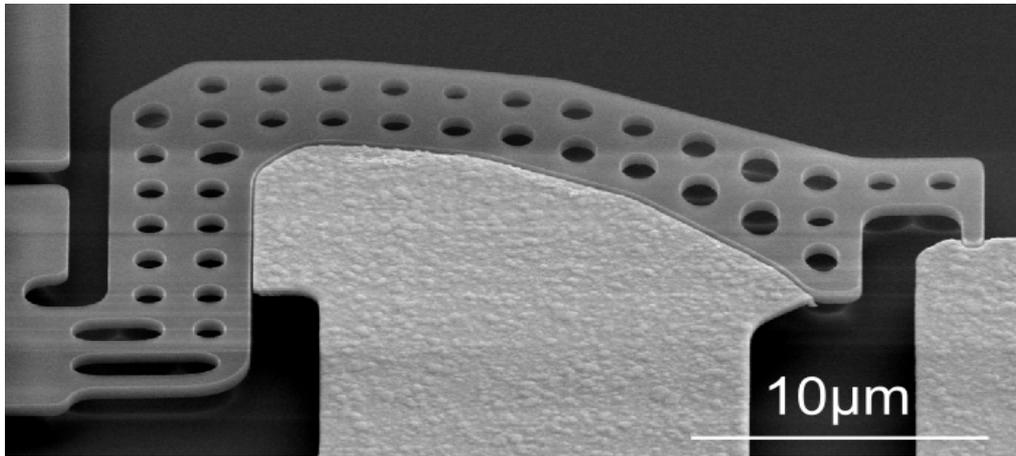
(source: F. Chen et al, ICCAD 2008)



□ NEM relay advantages

- practically zero leakage
- Very steep slope for turn-on/-off transient
- high on-current

NEM Relay Technology

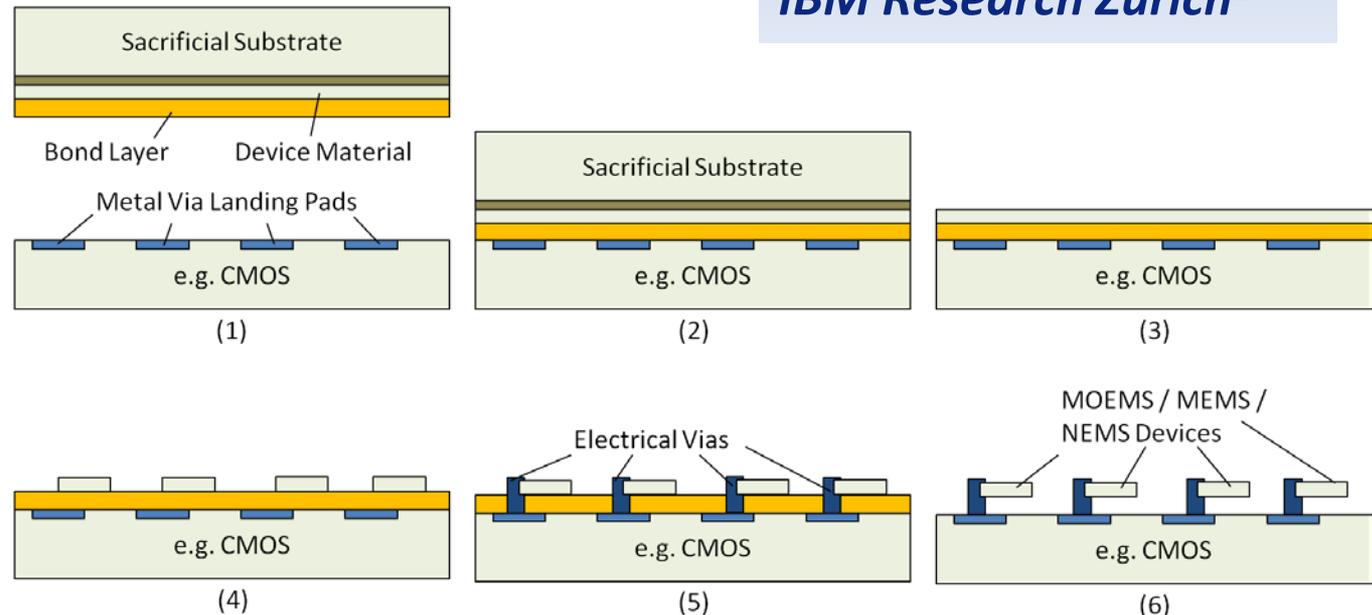


**In-plane switch,
fabricated using
standard lithography in
NEMIAC project; nm
gap using sacrificial
layer**

*courtesy D. Grogg et al.
IBM Research Zurich¹*

**Long term
integration
plan**

*courtesy F.
Niklaus et al.
KTH, Sweden*



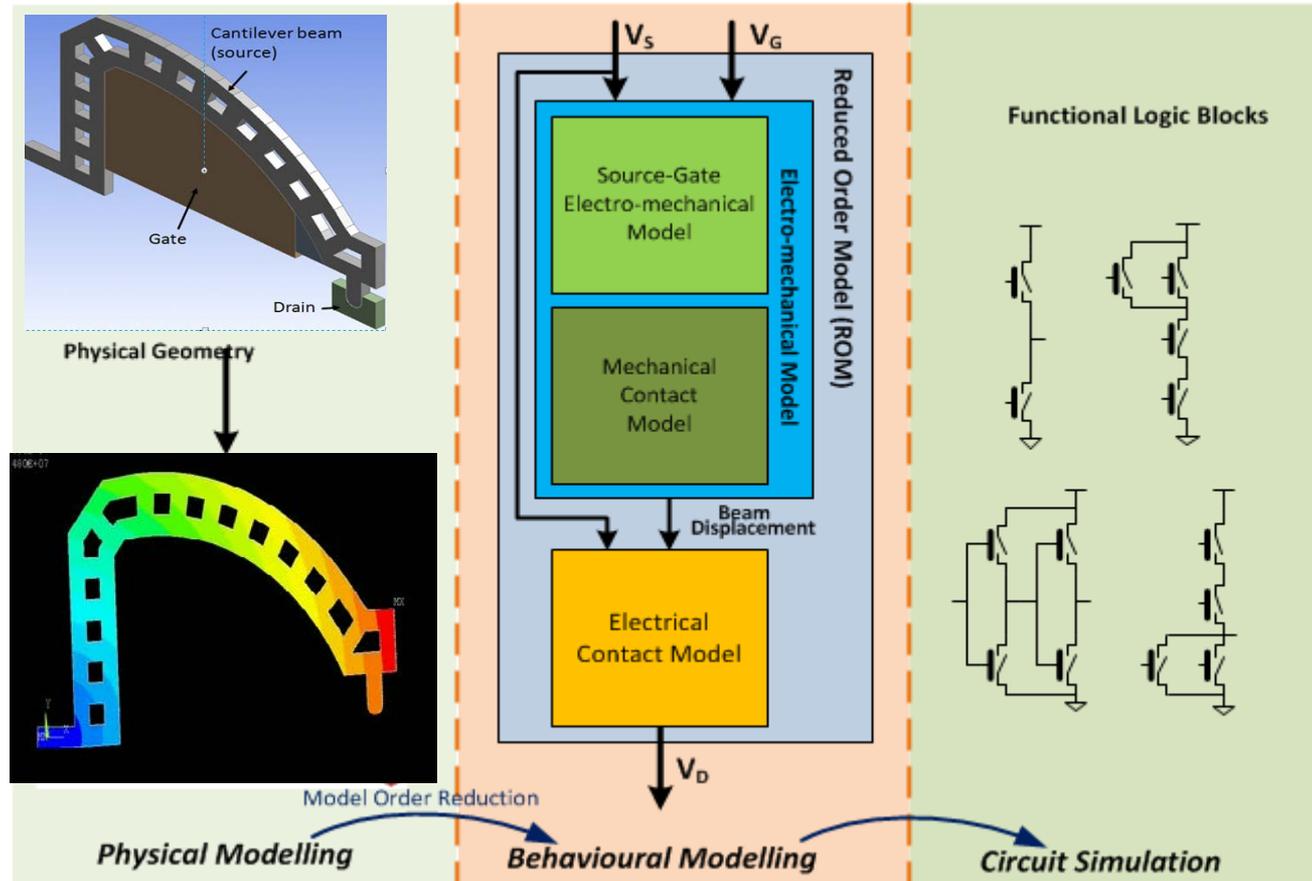
1. D. Grogg et al., "Curved cantilever design for a robust and scalable microelectromechanical switch," *Int. Conf. on Electron, Ion, and Photon Beam Technology and Nanofabrication*, Waikoloa, Hawaii, 2012.

DP, D43D Jun 2013

microelectronics research group

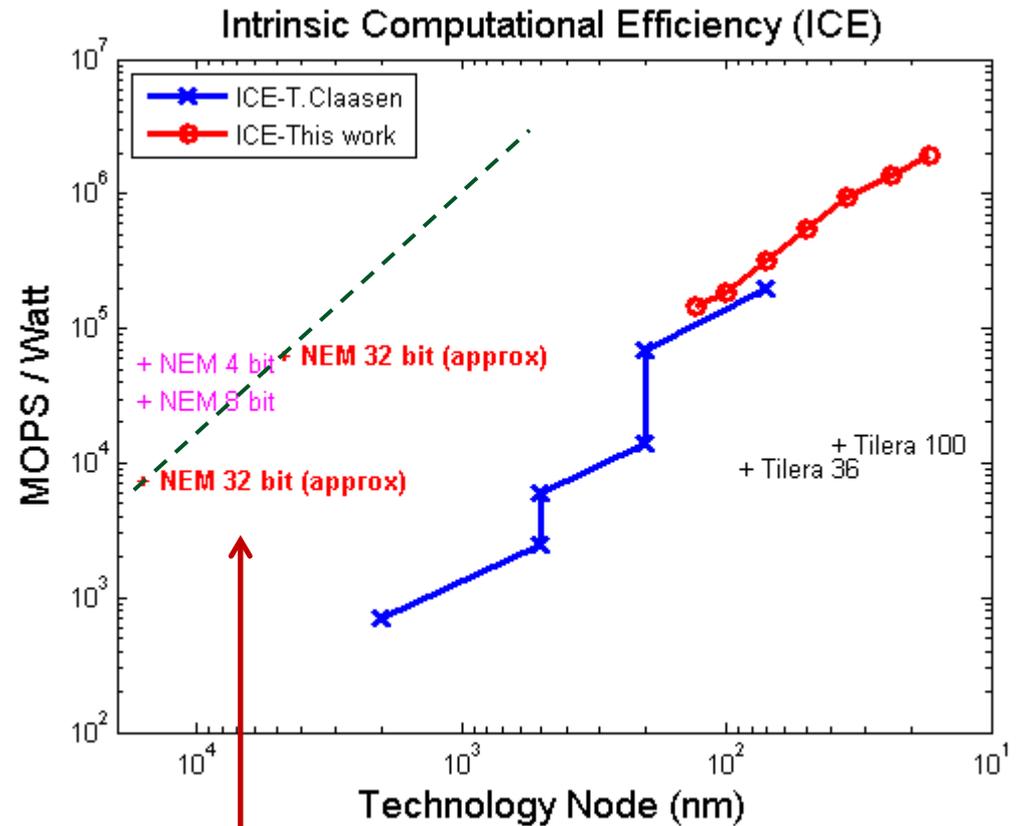
NEM Relay Modelling

□ FEA to Reduced Order Model to Circuit Model



ICE with NEM Logic

- ❑ **NEM “tech node” is much larger than CMOS**
 - Devices fabricated at 17 μm and 5 μm cantilever length
- ❑ **Miniaturisation increases speed and reduces energy**
 - No straightforward analogue to scaling for CMOS
- ❑ **Trajectory is promising**
 - Ultra-low power technology for low latency, low throughput applications

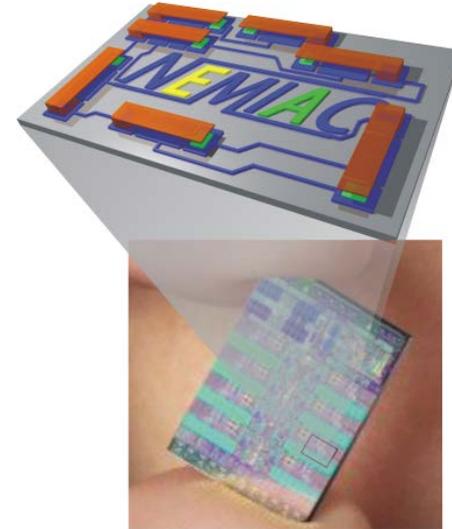


- Ripple-carry architecture and worst-case energy
- Device models at 17 μm and 5 μm silicon qualified
- 4 and 8-bit adder energy at 17 μm based on accurate circuit model
- 32-bit adders based on scaling

Acknowledgements

□ NEMIAC project

- EU FP7 Strep: Grant No. 288670

The logo for the NEMIAC project, featuring the word "NEMIAC" in a stylized, italicized font. The letters are blue, with the 'E' and 'I' highlighted in yellow and green respectively.

□ ELITE Project

- EU FP7 Strep: Grant No. 215030

